

FIG. 1

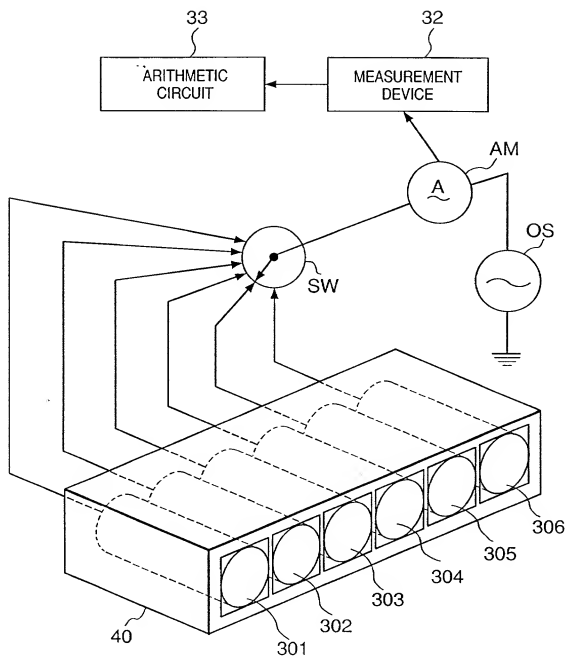


FIG. 2

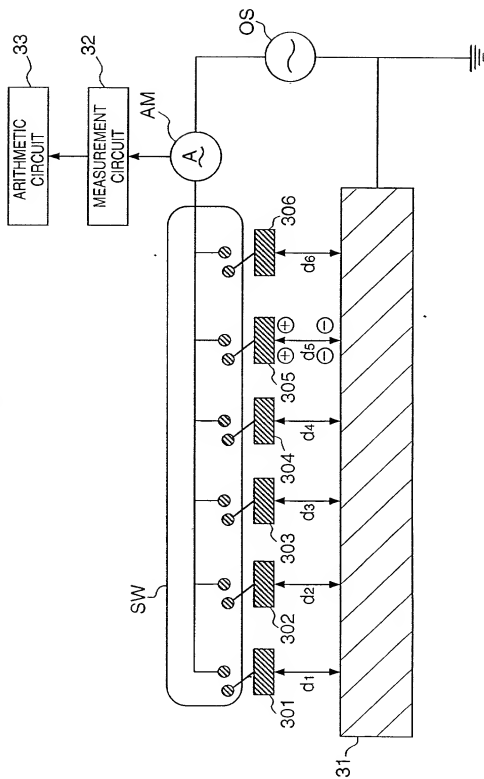


FIG. 3

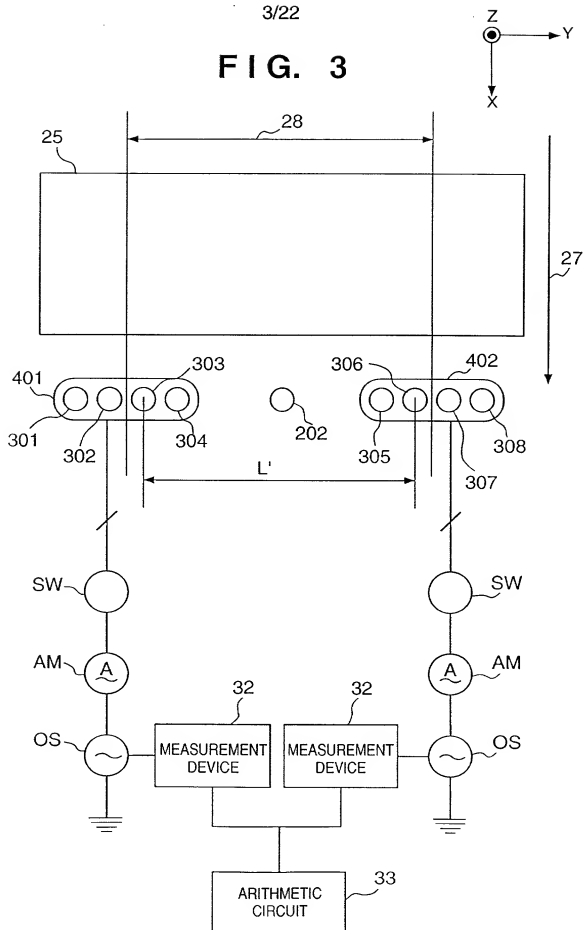


FIG. 4

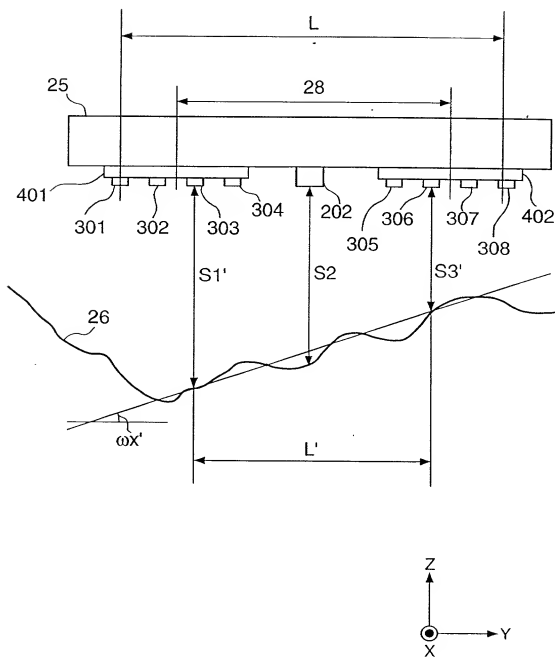
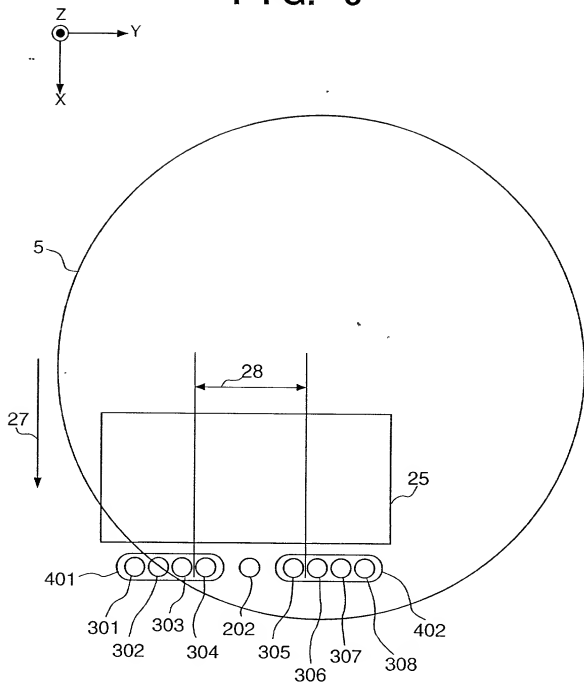


FIG. 5



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FIG. 6

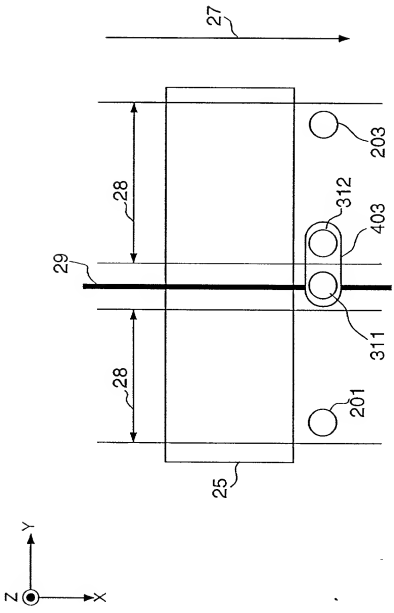


FIG. 7

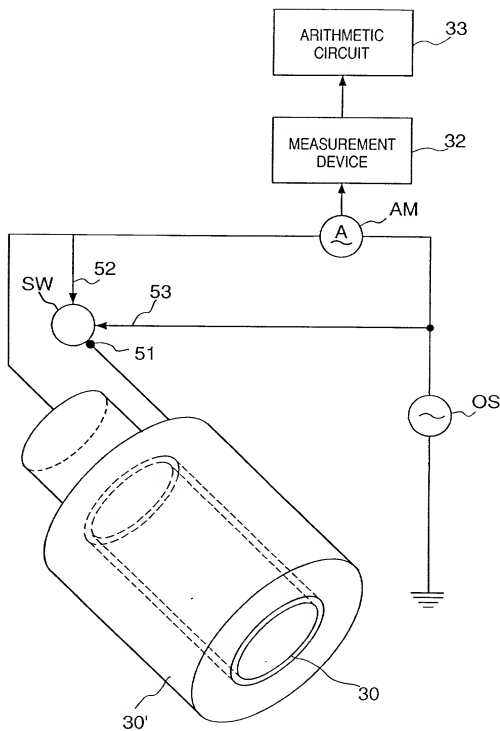
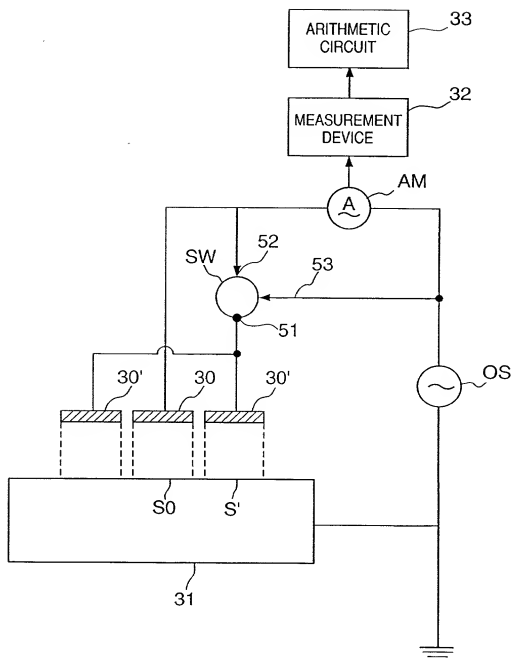
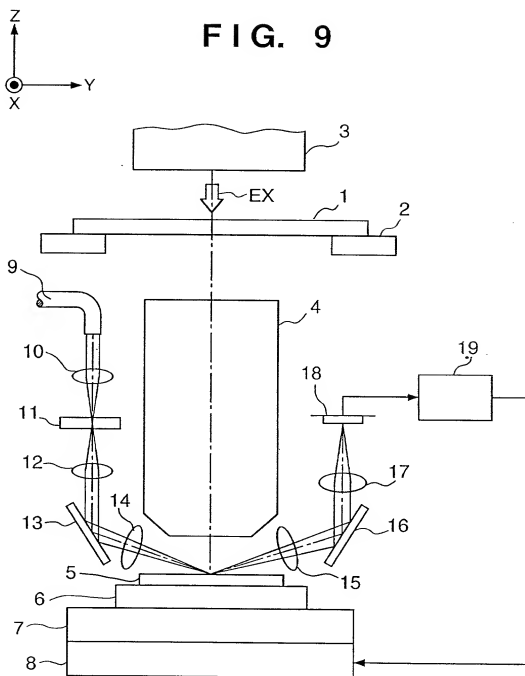


FIG. 8



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FIG. 9



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FIG. 10

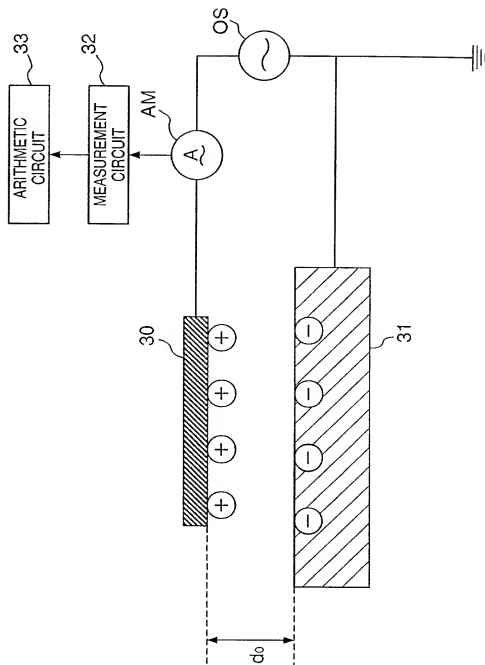
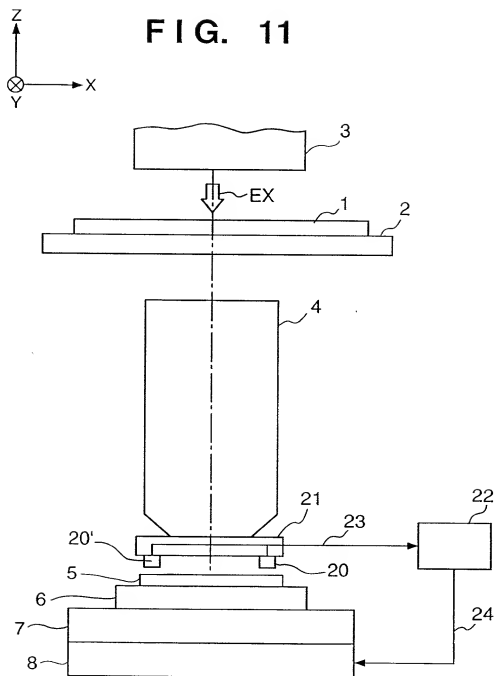


FIG. 11



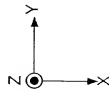


FIG. 12

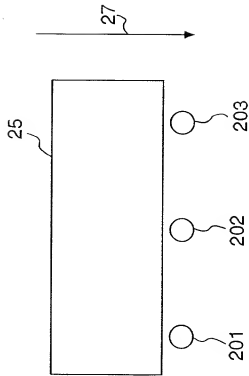


FIG. 13

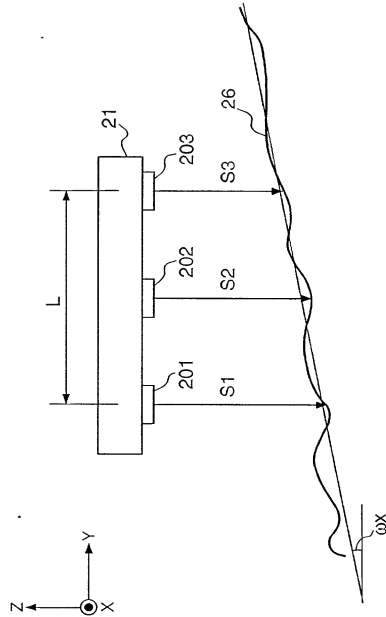


FIG. 14

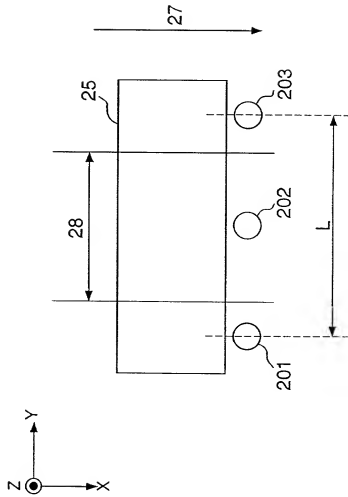


FIG. 15

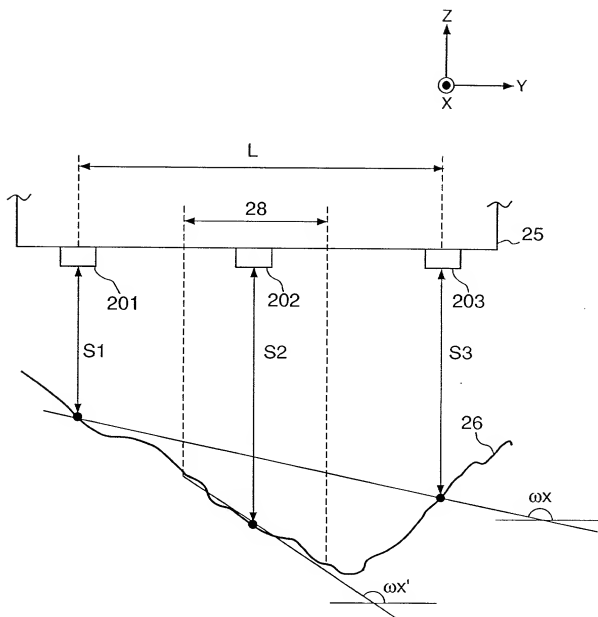


FIG. 16

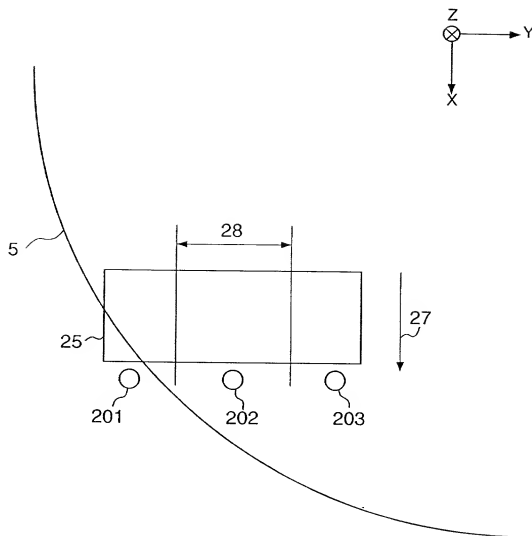
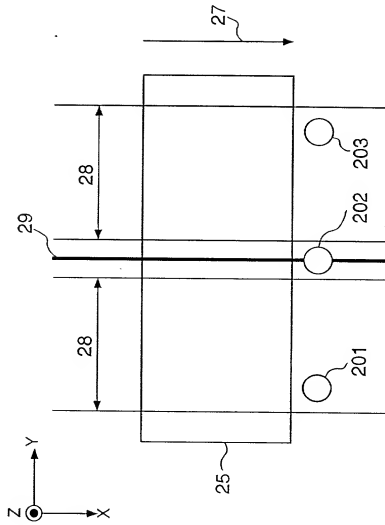


FIG. 17



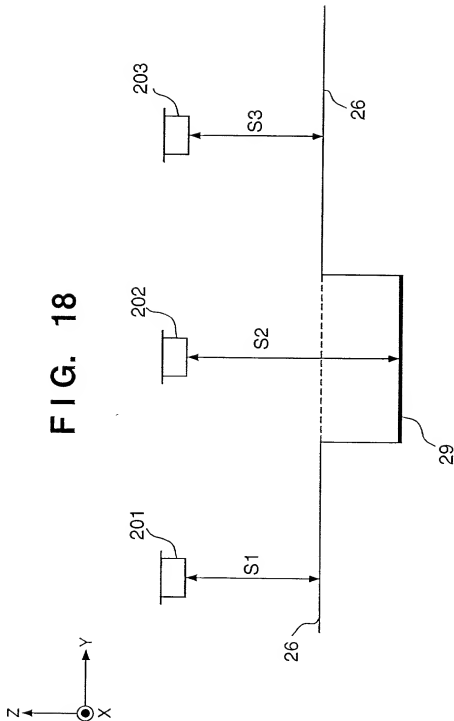
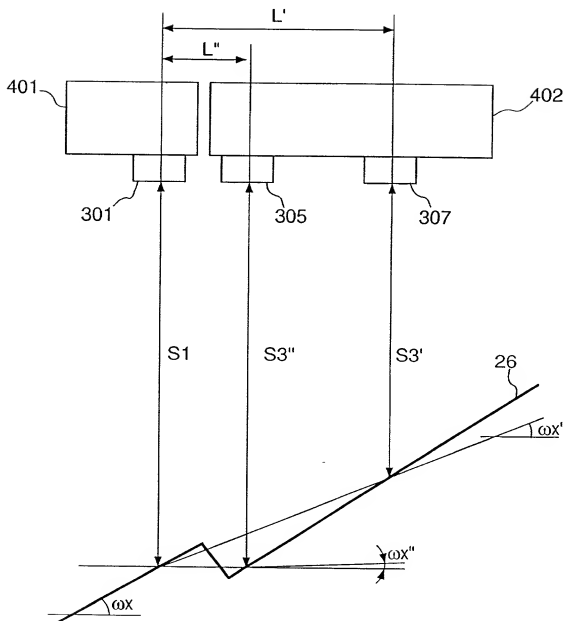


FIG. 19



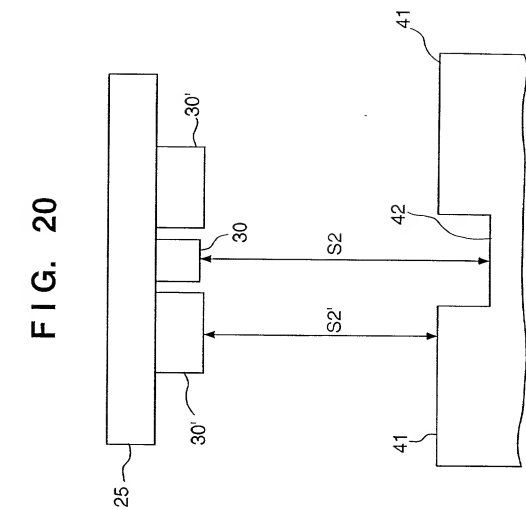
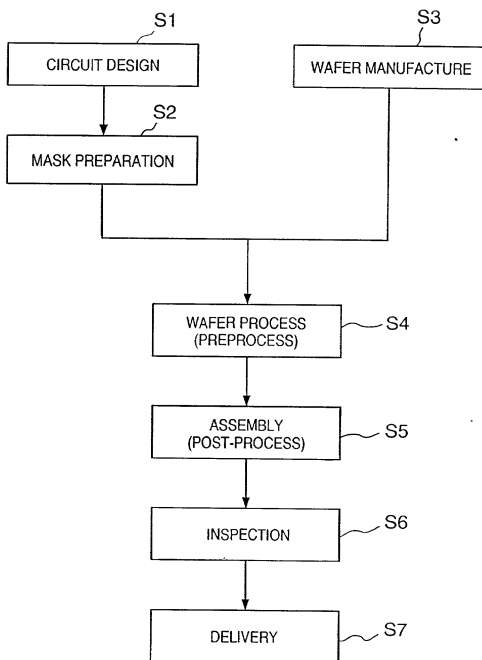


FIG. 21



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

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FIG. 22

